ABSTRACT

The invention pertains to a process for the production of particle beam systems (10-10'''', 12-12''), in which at least one first particle beam system (10-10'''') is produced on a first substrate (14) by computer-guided particle beam-induced deposition, and the minimum of one first particle beam system (10-10'''') is used to produce at least one second particle beam system (12-12'') on at least one second substrate (16) by computer-guided particle beam-induced deposition. The inventive process makes it possible to produce a large number of particle beam systems in a relatively short time.

(Figure 1)